

Errata

Page 30, line 11 is corrected from

“enhanced chemical vapour deposition (CVD) on Si wafer with metal catalyst layer (Ni).“

to

“enhanced chemical vapour deposition (CVD) on the surface of Si/SiO₂ substrate covered with Ti (5 nm thickness) with the aid of iron catalyst.“

Page 49, Figure 21: the title of the y axis is corrected from “Current [μ A]” to “Current [nA]”

Page 50, Figure 22: the title of the y axis is corrected from “Current [μ A]” to “Current [$1e^{-8}$ A]”